

	Hits	Search Text	DBs
62	90	((EUV or UV or VUV or DUV or X\$2ray) near9 (laser or ablat\$4 or irradiat\$4 or illuminat\$4 or expos\$4) near12 (resist or photoresist) near10 (remain\$3 or residu\$5) near19 develop\$5 near12 (remov\$5))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
63	87	((((resist or photoresist) near3 pattern\$4) same (irradiat\$4 or illuminat\$4 or expos\$4) same (remov\$5 or eliminat\$4) same (residu\$5 or remain\$5) same (develop\$5 or TMAH)) and ((ultraviolet or UV or VUV or EUV or X\$2ray or DUV) near9 (laser or ablat\$4 or irradiat\$4 or illuminat\$4 or expos\$4) near12 (resist or photoresist) near10 (remain\$3 or residu\$5) near19 develop\$5)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
64	81	((((resist or photoresist) near3 pattern\$4) same (irradiat\$4 or illuminat\$4 or expos\$4) same (remov\$5 or eliminat\$4) same (residu\$5 or remain\$5) same (develop\$5 or TMAH)) and ((UV or ultraviolet) near9 (laser or ablat\$4 or irradiat\$4 or illuminat\$4 or expos\$4) near12 (resist or photoresist) near10 (remain\$3 or residu\$5) near19 develop\$5)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB